L Number	Hits	Search Text	DB	Time stamp
1	16	jp-2000159758-\$.did. jp-2002131917-\$.did.	USPAT;	2003/10/24 13:56
		jp-11305444-\$.did. jp-2001142213-\$.did.	US-PGPUB;	
		jp-2001188346-\$.did. jp-2001240625-\$.did.	EPO; JPO;	
		jp-2002116546-\$.did. jp-2002296783-\$.did.	DERWENT	
2	· 38	(US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or	USPAT;	2003/10/24 14:19
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	US-PGPUB;	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or	JPO	
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or	1	
	-	US-20010033989-\$ or US-20010018162-\$ or		,
		US-20010010890-\$ or US-20010003640-\$).did. or		
		(JP-2001142213-\$ or JP-2001188346-\$ or		
		JP-2001240625-\$).did.		
3	41	(((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/10/24 14:20
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
		US-20020051936-\$ or US-20020051935-\$ or		
		US-20020048724-\$ or US-20020009668-\$ or		
		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) (((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))		

East Don't Remove

4	18	((((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/10/24 14:20
	1	and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
	1	US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or	,	
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		•
		US-20020051936-\$ or US-20020051935-\$ or		
	Ì	US-20020048724-\$ or US-20020009668-\$ or		
		US-20020009667-\$ or US-20020004569-\$ or		ĺ
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) (((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
	1	AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		,
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))) not		
		((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or		·
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or		
٠.		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		
				•
		US-20020132181-\$ or US-20020098441-\$ or		1
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		,
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did. or		
		(JP-2001142213-\$ or JP-2001188346-\$ or		
		JP-2001240625-\$).did.)		
5	341	(resist photoresist) and (lactone) and ((maleic adj	USPAT;	2003/10/24 14:41
•		anhydride) (maleimide)) and (norbornene norbornyl)	US-PGPUB;	
		annyunder (malemider) and (norbornene norbornyr)		
			EPO; JPO;	
			DERWENT	
5	17155	(acid photoacid) near generat\$4	USPAT;	2003/10/24 14:41
·			US-PGPUB;	
			EPO; JPO;	
		·	DERWENT	
_	07000			0000/10/04 14 44
7	87099	positive near5 (composition working image pattern type)	USPAT;	2003/10/24 14:44
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
0	4069	((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
8	4009			2000/10/23 13.30
		(composition working image pattern type))	US-PGPUB;	
			EPO; JPO;	
	1	I .	DERWENT	1

9	235	(((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
		(composition working image pattern type))) and ((resist	US-PGPUB;	
		photoresist) and (lactone) and ((maleic adj anhydride)	EPO; JPO;	
		(maleimide)) and (norbornene norbornyl))	DERWENT	
10	202	((((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
		(composition working image pattern type))) and ((resist	US-PGPUB;	
		photoresist) and (lactone) and ((maleic adj anhydride)	EPO; JPO;	
		(maleimide)) and (norbornene norbornyl))) not	DERWENT	
		((jp-2000159758-\$.did. jp-2002131917-\$.did.		
		jp-11305444-\$.did. jp-2001142213-\$.did.		
		jp-2001188346-\$.did. jp-2001240625-\$.did.		
	i	jp-2002116546-\$.did. jp-2002296783-\$.did.)		
	'	((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or		
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or		
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
	•	US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
;		US-5929271-\$ or US-5910392-\$).did. or		
1		(US-20020009666-\$ or US-20010041303-\$ or		
,		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		,
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did. or		
		(JP-2001142213-\$ or JP-2001188346-\$ or		
	•	JP-2001240625-\$).did.) (((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and		
		(((ÚS-6403280-\$ or US-6388101-\$ or US-6329125-\$ or		
•		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		,
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
	,	US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		1
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
	}	US-20010010890-\$ or US-20010003640-\$).did.) (((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
•		and (SATO-KENICHIRO		· ·
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
	l ,	AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
1.1	70107	AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))))	LICDAT.	2003/10/24 14:47
11	70187	nitrogen and surfactant	USPAT;	2003/10/24 14:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	

12	113	(nitrogen and surfactant) and (((((acid photoacid) near	USPAT;	2003/10/24 16:20
		generat\$4) and (positive near5 (composition working image	US-PGPUB;	<u>'</u>
		pattern type))) and ((resist photoresist) and (lactone) and	EPO; JPO;	
		((maleic adj anhydride) (maleimide)) and (norbornene	DERWENT	
		norbornyl))) not ((jp-2000159758-\$.did.		
		jp-2002131917-\$.did. jp-11305444-\$.did.		•
		jp-2001142213-\$.did. jp-2001188346-\$.did.		
	•		·	
		jp-2001240625-\$.did. jp-2002116546-\$.did.		
		jp-2002296783-\$.did.) ((US-6448420-\$ or US-6280898-\$		
		or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or		,
		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or	•	•
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or		•
1		(US-20020009666-\$ or US-20010041303-\$ or		
1		·		
ŀ		US-20020132181-\$ or US-20020098441-\$ or		,
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		,
İ		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
l		US-20010010890-\$ or US-20010003640-\$).did. or		
i		(JP-2001142213-\$ or JP-2001188346-\$ or		'
		JP-2001240625-\$).did.) (((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
l		alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and		
		(((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or		
		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		
i		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
		1 '		
•		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		,
.		US-20010013769-\$ of US-20010018102-\$ of US-20010010018090-\$ or US-20010003640-\$).did.) ((((((resin	1	
ĺ				
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		and (SATO-KENICHIRO		
1		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
.		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))))))		
13	2	("6579659").PN.	USPAT;	2003/10/24 16:5
	۷	(00.7007)	US-PGPUB;	2003/10/24 10.3
1		,		
1	•		EPO; JPO;	
			DERWENT	
14	0	6579659.URPN.	USPAT	2003/10/24 16:2
15	6	("5968713" "6013416" "6068512" "6200725"	USPAT	2003/10/24 16:2
1		"6280898" "6492091" "2001/0003640").PN.		
16	6706	(fluorine silicon) near5 surfactant	USPAT;	2003/10/24 17:0
-0	0700	(maxime sincon) near surfactant	US-PGPUB;	2000,10,2117.0.
			1	
!			EPO; JPO;	

17	4693585	conventional improvement enhance enhancement improve benefit beneficial	USPAT; US-PGPUB;	2003/10/24 16:57
			EPO; JPO; DERWENT	
18 -	930	((fluorine silicon) near5 surfactant) same (conventional	USPAT;	2003/10/24 16:59
		improvement enhance enhancement improve benefit	US-PGPUB;	
		beneficial)	EPO; JPO;	
		·	DERWENT	•
19	0	(((fluorine silicon) near5 surfactant) same (conventional	USPAT;	2003/10/24 17:00
		improvement enhance enhancement improve benefit	US-PGPUB;	
		beneficial)) and (positive near5 (composition working	EPO; JPO;	
		image pattern type)) and ((acid photoacid) near generat\$4)	DERWENT	
		and ((resist photoresist) and (lactone) and ((maleic adj		·
20	49	anhydride) (maleimide)) and (norbornene norbornyl)) (((fluorine silicon) near5 surfactant) same (conventional	USPAT;	2003/10/24 17:10
	1)	improvement enhance enhancement improve benefit	US-PGPUB;	2003/10/24 17.10
		beneficial)) and (positive near5 (composition working	EPO; JPO;	•
		image pattern type)) and ((acid photoacid) near generat\$4)	DERWENT	
21	24	(((fluorine silicon) near5 surfactant) same (conventional	USPAT	2003/10/24 17:06
	į	improvement enhance enhancement improve benefit		
		beneficial)) and (positive near5 (composition working		
<u> </u>		image pattern type)) and ((acid photoacid) near generat\$4)		
22	2	("4822713").PN.	USPAT;	2003/10/24 17:06
	!		US-PGPUB;	
			EPO; JPO; DERWENT	
23	138	(fluorine-type silicon-type) near5 surfactant	USPAT;	2003/10/24 17:10
25	150	(Huorme-type smeon-type) hears surfactant	US-PGPUB;	2003/10/24 17.10
			EPO; JPO;	
			DERWENT	
24	4	((fluorine-type silicon-type) near5 surfactant) and (positive	USPAT;	2003/10/24 17:11
		near5 (composition working image pattern type)) and ((acid	US-PGPUB;	
		photoacid) near generat\$4)	EPO; JPO;	
0.6	10050		DERWENT	000000000000000000000000000000000000000
26	13952	(((fluorine-type silicon-type) near5 surfactant) same	USPAT; US-PGPUB;	2003/10/24 17:11
		(conventional improvement enhance enhancement improve benefit beneficial)) amd (positive near5 (composition	EPO; JPO;	
	, ·	working image pattern type)) and ((acid photoacid) near	DERWENT	·
		generat\$4)	DERVIERVA	
27	0	(((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:12
		(conventional improvement enhance enhancement improve	US-PGPUB;	
		benefit beneficial)) and (positive near5 (composition	EPO; JPO;	
		working image pattern type)) and ((acid photoacid) near generat\$4)	DERWENT	
28	1	(((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:12
-	*	(conventional improvement enhance enhancement improve	US-PGPUB;	2000,10,2117.12
		benefit beneficial)) and (positive near5 (composition	EPO; JPO;	
		working image pattern type))	DERWENT	
25	18	((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:12
	,	(conventional improvement enhance enhancement improve	US-PGPUB;	
		benefit beneficial)	EPO; JPO;	
	10/0077		DERWENT	2002/10/24 12.55
•	1863077	resin resist photoresist	USPAT; US-PGPUB;	2003/10/24 13:55
			EPO; JPO;	
			DERWENT	
-	8221	(resin resist photoresist) and (acid near generat\$4)	USPAT;	2002/10/10 12:17
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	
			EPO; JPO;	
			DERWENT	

•	1522	"3" and (positive near composition)	USPAT;	2002/10/10 12:24
			US-PGPUB;	
			EPO; JPO;	
	•		DERWENT	•
-	203	((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 12:24
		(positive near composition)	US-PGPUB;	
			EPO; JPO;	
	:		DERWENT	
-	3892	((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 12:43
		(positive)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	("us-20010039080-A1.did.").PN.	USPAT;	2002/10/10 12:32
		,	US-PGPUB;	
			EPO; JPO;	
		·	DERWENT	
_	2	("20010039080").PN.	USPAT;	2002/10/10 12:32
	2	(20010037000).111.	US-PGPUB;	2002/10/10 12:32
			EPO; JPO;	
	-		DERWENT	
	0	20010039080.URPN.	USPAT	2002/10/10 12:43
-	_		USPAT;	1 -
-	801	(((resin resist photoresist) and (acid near generat\$4)) and	USPAT; US-PGPUB;	2002/10/10 14:19
		(positive)) and (norborn\$5 alicyclic)	l '	
			EPO; JPO;	
	000		DERWENT	0000/10/04 14 45
-	288	((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/10/24 14:45
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)	EPO; JPO;	
		•	DERWENT	
-	721	SATO-KENICHIRO	USPAT;	2002/10/15 14:57
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	US-PGPUB;	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F	EPO; JPO;	
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F	DERWENT	
-	30	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:41
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) and (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)		
	258	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 16:06
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
	1	develop\$4)) not ((((((resin resist photoresist) and (acid near	EPO; JPO;	
	1	generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and	DERWENT	
		(alkaline adj develop\$4)) and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
	1	AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))		
_	79	(((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 14:57
_	',	(((((resin resist photoresist) and (acid near generation)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2002,10,13 14.37
•		develop\$4)) not ((((((resin resist photoresist) and (acid near	EPO; JPO;	
		report \$41) and (notified 1) and (nother \$5 aliceles)	DERWENT	
	1	generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and	DEKAARIAT	
	1	(alkaline adj develop\$4)) and (SATO-KENICHIRO		,
	1	SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
	1	AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)	LICDAT	2002/10/15 15 00
-	289	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 15:00
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)	EPO; JPO;	
			DERWENT	

SATO-KENICHIRO C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TO-SHIAKI AOAI-TO		·	_			
AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUGI-PHOTO-F AOAI-TOSHIAKI CO-FUJI-PHOTO-F (((((resin resist photoresist) and (acid near generat54)) and (avelap54)) non ((SATO-KENICHIRO) and (alakine adj develop54)) non (SATO-KENICHIRO) - 79 (((((resin resist) photoresist) and (acid near generat54)) and (positive)) and (norborn55 slicyclic)) and (alakine adj develop54)) not ((((resin resist) photoresist) and (acid near generat54)) and (positive)) and (norborn55 slicyclic)) and (alakine adj develop54)) not ((((resin resist) photoresist)) and (acid near generat54)) and (positive)) and (norborn55 slicyclic)) and (alakine adj develop54)) not (SATO-KENICHIRO) - AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUGI-PHOTO-F AOAI-TOSHIAKI-CO-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUGI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUGI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-PHOTO-F AOAI-TOSHIAKI-CO-FUJI-PHOTO-CI-P	Γ	•	723			2002/10/15 15:01
AOAI-TOSHIAKIC-Co-FUII-PHOTO-F 2002/10/15 15:01				· ·		
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SATO-KENICHIRO-Co-FUII-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-Co-FUEI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-Co-FUEI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-Co-FUEI-PHOTO-F AOAI-TOSHIAKI AOAI-TOSHIAKI-Co-FUEI-PHOTO-F P (((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS alicyclic)) and (alkaline adj develop\$4)) not ((((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS) alicyclic) and (alkaline adj develop\$4)) not (SATO-KENICHIRO-Co-FUII-PHOTO-F))) and (lactone) ((((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS alicyclic)) and (alkaline adj develop\$4)) not (SATO-KENICHIRO-Co-FUII-PHOTO-F) not ((((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS alicyclic)) and (alkaline adj develop\$4)) and (sato-P) (((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO-Co-FUII-PHOTO-F)) not ((((((tresin resist photoresist) and (acid near generats4)) and (positive)) and (norbornSS alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO SATO-KENICHIRO-CO-FUII-PHOTO-F)) and (lactone) (US-20010039080-S.did. 10				(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
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(positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resin photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-CO-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI AOAI-TOSHIAKI (CO-FUGI-PHOTO-F AOAI-TOSHIAKI				AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)		
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2				AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
Cresist photoresist) and (norborn\$5) and (\$5acid near generat\$3)				AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone))		
S49			2	US-20010039080-\$.did.	USPAT;	2002/10/15 19:07
- 549 (resist photoresist) and (norborn\$5) and (\$5acid near generat\$3) - 96 ((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3)) - 71 (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adj anhydride) - 7 "6284429" - 2 ("6284429").PN. DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB					US-PGPUB;	
- 549 (resist photoresist) and (norborn\$5) and (\$5acid near generat\$3) - 96 ((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3)) - 71 (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and ((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adj anhydride) - 7 "6284429" - 2 ("6284429").PN. 2002/10/16 11:41 US.PGPUB; EPO; JPO; DERWENT					EPO; JPO;	
generat\$3)					DERWENT	
Post		-	549		USPAT;	2002/10/16 11:41
Post				generat\$3)		,
- 96 ((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3)) - 71 (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adj anhydride) - 7 "6284429" - 2 ("6284429").PN. 2002/10/16 11:44 USPAT; US-PGPUB; EPO; JPO; DERWENT						
generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3)) (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive 1 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) 1 7 "6284429" 2 ("6284429").PN. 2 ("6284429").PN. US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;				,	ľ	
improv\$5 benef\$3)) (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) - 7 "6284429" 7 "6284429" 2 ("6284429").PN. EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;		-	96			2002/10/16 11:44
- 71 (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) - 7 "6284429" - 2 ("6284429").PN. DERWENT USPAT; US-PGPUB; EPO; JPO;						
- 1 (((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) - 7 "6284429" - 2 ("6284429").PN. 2 ("6284429").PN. 2 ("6284429").PN. 2 ("6284429").PN. 2 ("6284429").PN. 2 (2003/10/24 14:20 US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;				improv\$5 benef\$3))		
generat\$3)) and ((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive - 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) - 7 "6284429" - 2 ("6284429").PN. US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWE						
improv\$5 benef\$3))) and positive 325 norbornene same (acrylate methacrylate) same (maleic adj anhydride) - 7 "6284429" 2 ("6284429").PN. EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;		-	71			2003/10/24 14:20
- 325 norbornene same (acrylate methacrylate) same (maleic adj anhydride) - 7 "6284429" - 2 ("6284429").PN. DERWENT USPAT; US-PGPUB; EPO; JPO;						
- 325 norbornene same (acrylate methacrylate) same (maleic adjanhydride) - 7 "6284429" - 2 ("6284429").PN. 2 (002/10/16 11:54 US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;				improv\$5 benef\$3))) and positive		
anhydride) anhydride) US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; USPAT; US-PGPUB; EPO; JPO;			,	•		
EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;		-	325			2002/10/16 11:54
- 7 "6284429" - 2 ("6284429").PN. DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;				anhydride)		
- 7 "6284429" - 2 ("6284429").PN. USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; EPO; JPO;						
- 2 ("6284429").PN. US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; EPO; JPO;					1	
EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;		-	7	"6284429"		2002/10/16 14:53
DERWENT USPAT; 2002/10/16 14:53 US-PGPUB; EPO; JPO;					l .	
- 2 ("6284429").PN. USPAT; US-PGPUB; EPO; JPO;						
US-PGPUB; EPO; JPO;						
EPO, JPO;		-	2	("6284429").PN.		2002/10/16 14:53
				·		. !
DERWENT						
	L			<u> </u>	DERWENT	

	35	(US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or	USPAT;	2003/04/29 09:39
•		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or	US-PGPUB	
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		,
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did.		
-	343	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:43
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))	EPO; JPO;	
			DERWENT	
-	44	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/10/24 14:39
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) and (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)		
-	118	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:44
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)	EPO; JPO;	
			DERWENT	
_	77	((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or	USPAT;	2003/04/29 09:44
	,,	US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or	US-PGPUB;	2003/01/27 07.11
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or	EPO; JPO;	
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or	DERWENT	
			DERWEINT	
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
	İ	US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or	,	
		US-20010010890-\$ or US-20010003640-\$).did.) ((((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
	1	AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))	-	

	38	(((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/10/24 14:19
	. 30	and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2003/10/2111.17
		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or	DERWENT	•
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
		US-20020051936-\$ or US-20020051935-\$ or		
		US-20020048724-\$ or US-20020009668-\$ or		
	,	US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) (((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO	·	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))		
<u>-</u>	157	(((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/04/29 09:44
	137	and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2000,0 42,0 0,111
		develop\$4))) and (lactone)) (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or	DERWEIT	
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
	1	US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
		US-20020051936-\$ or US-20020051935-\$ or		
		US-20020048724-\$ or US-20020009668-\$ or		
		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) ((((((resin resist photoresist) and		,
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
1 '		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	1	
	i			
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		